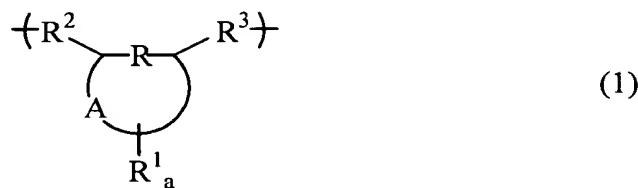


The following listing of claims will replace all prior versions, and listings, of claims in the application:

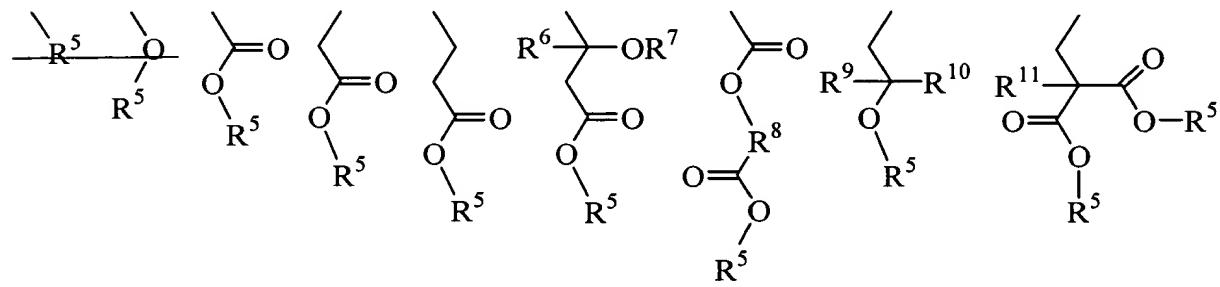
**Listing of Claims:**

1. (Currently Amended): A polymer comprising recurring units of a compound of formula (1):



wherein

$A$  is a divalent aliphatic or alicyclic hydrocarbon group of 2 to 20 carbon atoms,  
 $R^1$  is selected from formulae (3)-1, (3)-2, (3)-3, (3)-4, (3)-5, (3)-6, (3)-7, (3)-8, and (3)-9



(3)-1 (3)-2 (3)-3 (3)-4 (3)-5 (3)-6 (3)-7 (3)-8 (3)-9

"a" is a positive number of 1 to 3,

$R$  is a single bond, methylene group, oxygen atom, NH group or sulfur atom,

$R^2$  and  $R^3$  each are a single bond or methylene group,

$R^5$  is a fluorinated alkyl group which optionally contains an ether or ester bond,

$R^6$  and  $R^{11}$  are, each independently, hydrogen or a straight alkyl group of 1 to 10 carbon atoms,

$R^7$  is hydrogen, a straight alkyl group of 1 to 10 carbon atoms, or  $-C=O-R^{12}$ ,

$R^{12}$  is hydrogen or a straight alkyl group of 1 to 10 carbon atoms, and

$R^8$  is an alkylene group of 1 to 10 carbon atoms, and

either one or both of R<sup>9</sup> and R<sup>10</sup> are alkyl groups of 1 to 5 carbon atoms having at least one fluorine atom substituted thereon.

2. (Original): The polymer of claim 1 further comprising recurring units containing acid labile groups.

3. (Previously Presented): A chemically amplified resist composition comprising the polymer of claim 1.

4. (Previously Presented): A chemically amplified positive resist composition comprising

- (A) the polymer of claim 1,
- (B) an organic solvent, and
- (C) a photoacid generator.

5. (Original): The resist composition of claim 4 further comprising a basic compound.

6. (Original): The resist composition of claim 4 further comprising a dissolution inhibitor.

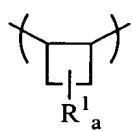
7. (Original): A process for forming a resist pattern comprising the steps of: applying the resist composition of claim 4 onto a substrate to form a coating, heat treating the coating and then exposing it to high-energy radiation having a wavelength of up to 180 nm or electron beams through a photo mask, and optionally heat treating the exposed coating and developing it with a developer.

8. (Cancelled):

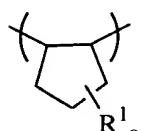
9. (Cancelled):

10. (Previously Presented): A polymer of claim 1, wherein R is a single bond or methylene.

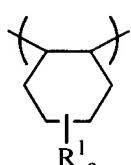
11. (Previously Presented): A polymer of claim 1, wherein the recurring units of formula (1) are selected from formulae (2)-1, (2)-2, (2)-3, (2)-4, (2)-5, (2)-6, (2)-7, (2)-8, and (2)-9



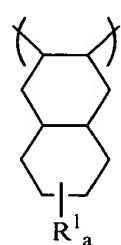
(2)-1



(2)-2



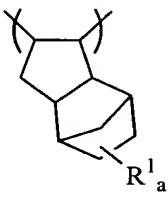
(2)-3



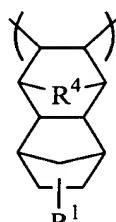
(2)-4



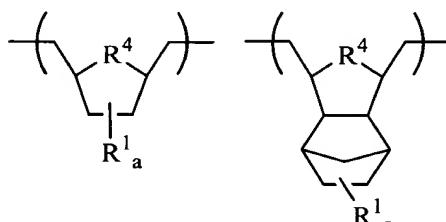
(2)-5



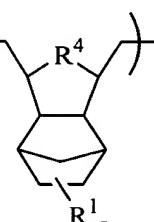
(2)-6



(2)-7



(2)-8



(2)-9

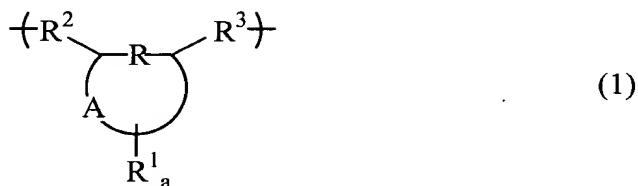
wherein

R<sup>4</sup> is a methylene group, oxygen atom, NH group or sulfur atom, and

“a” is a positive number of 1 to 3.

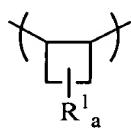
12. (Cancelled):

13. (Previously Presented): A polymer comprising recurring units of a compound of formula (1):

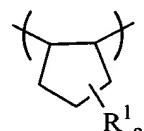


wherein A is a divalent aliphatic or alicyclic hydrocarbon group of 2 to 20 carbon atoms, R<sup>1</sup> is an alkyl group containing at least one fluorine atom, and which optionally contains a hetero atom, "a" is a positive number of 1 to 3, R is a single bond, methylene group, oxygen atom, NH group or sulfur atom, and R<sup>2</sup> and R<sup>3</sup> each are a single bond or methylene group,

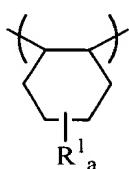
wherein the recurring units of formula (1) are selected from formulae (2)-1, (2)-2, (2)-3, (2)-4, (2)-5, (2)-6, (2)-7, (2)-8, and (2)-9



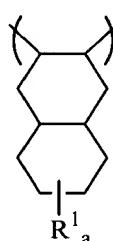
(2)-1



(2)-2



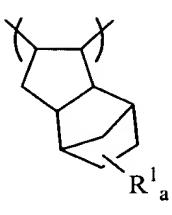
(2)-3



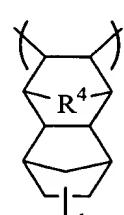
(2)-4



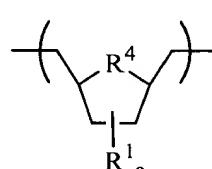
(2)-5



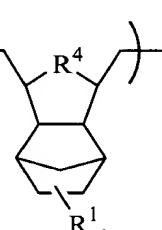
(2)-6



(2)-7



(2)-8



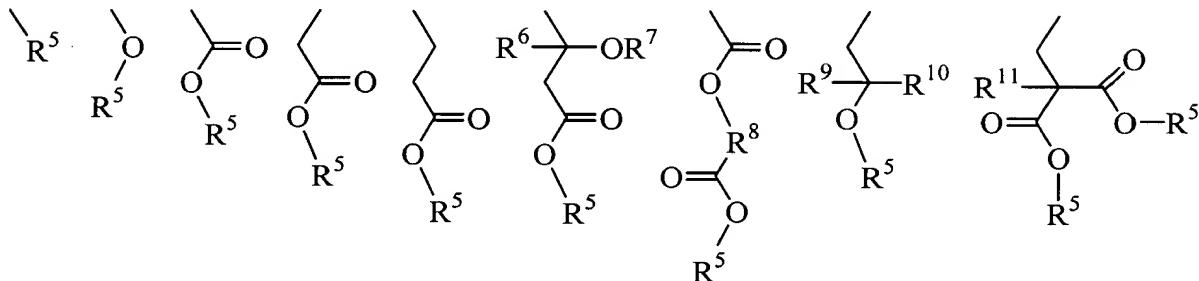
(2)-9

wherein

$R^4$  is a methylene group, oxygen atom, NH group or sulfur atom,

“a” is a positive number of 1 to 3,

$R^1$  is selected from formulae (3)-1, (3)-2, (3)-3, (3)-4, (3)-5, (3)-6, (3)-7, (3)-8, and (3)-9



(3)-1

(3)-2

(3)-3

(3)-4

(3)-5

(3)-6

(3)-7

(3)-8

(3)-9

$R^6$  and  $R^{11}$  are, each independently, hydrogen or a straight alkyl group of 1 to 10 carbon atoms,

$R^7$  is hydrogen, a straight alkyl group of 1 to 10 carbon atoms, or  $-C=O-R^{12}$ ,

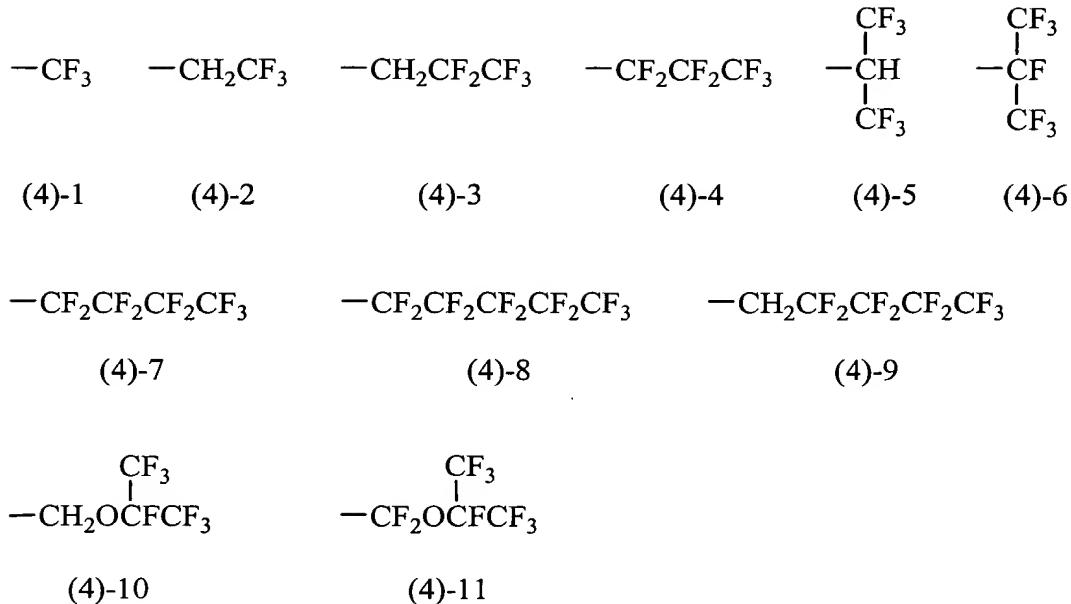
$R^{12}$  is hydrogen or a straight alkyl group of 1 to 10 carbon atoms, and

$R^8$  is an alkylene group of 1 to 10 carbon atoms,

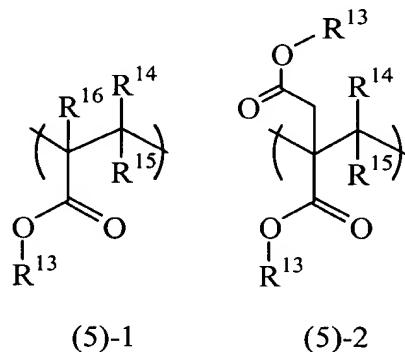
wherein either one or both of  $R^9$  and  $R^{10}$  are alkyl groups of 1 to 5 carbon atoms having at least one fluorine atom substituted thereon, and

$R^5$  is selected from formulae (4)-1, (4)-2, (4)-3, (4)-4, (4)-5, (4)-6, (4)-7, (4)-8, (4)-9, (4)-10

and (4)-11



14. (Previously Presented): A polymer of claim 1, further comprising recurring units of a (meth)acrylic compound of formula (5)-1 or (5)-2

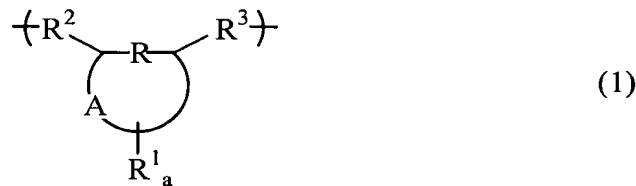


wherein

R¹³ is an acid labile group, and

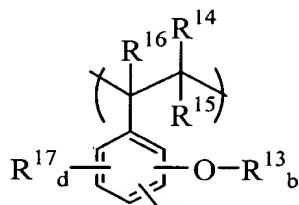
R¹⁴, R¹⁵ and R¹⁶ are, each independently, a hydrogen atom, fluorine atom, or a straight, branched or cyclic alkyl group of 1 to 10 carbon atoms, which are, each independently, optionally substituted with fluorine.

15. (Previously Presented): A polymer comprising recurring units of a compound of formula (1):



wherein A is a divalent aliphatic or alicyclic hydrocarbon group of 2 to 20 carbon atoms, R<sup>1</sup> is an alkyl group containing at least one fluorine atom, and which optionally contains a hetero atom, "a" is a positive number of 1 to 3, R is a single bond, methylene group, oxygen atom, NH group or sulfur atom, and R<sup>2</sup> and R<sup>3</sup> each are a single bond or methylene group,

said compound further comprising recurring units of a styrene compound of formula (6)



wherein

R<sup>13</sup> is an acid labile group,

R<sup>14</sup>, R<sup>15</sup> and R<sup>16</sup> are, each independently, a hydrogen atom, fluorine atom, or a straight, branched or cyclic alkyl group of 1 to 10 carbon atoms, which are, each independently, optionally substituted with fluorine,

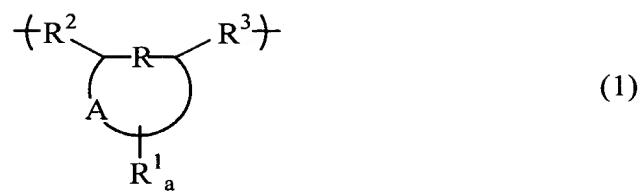
R<sup>17</sup> is a hydrogen atom, fluorine atom, or a straight, branched or cyclic alkyl group of 1 to 10 carbon atoms, which is optionally substituted with fluorine,

b is a positive number of 1 to 5, and

c and d are, each independently, 0 or a positive number of 1 to 4.

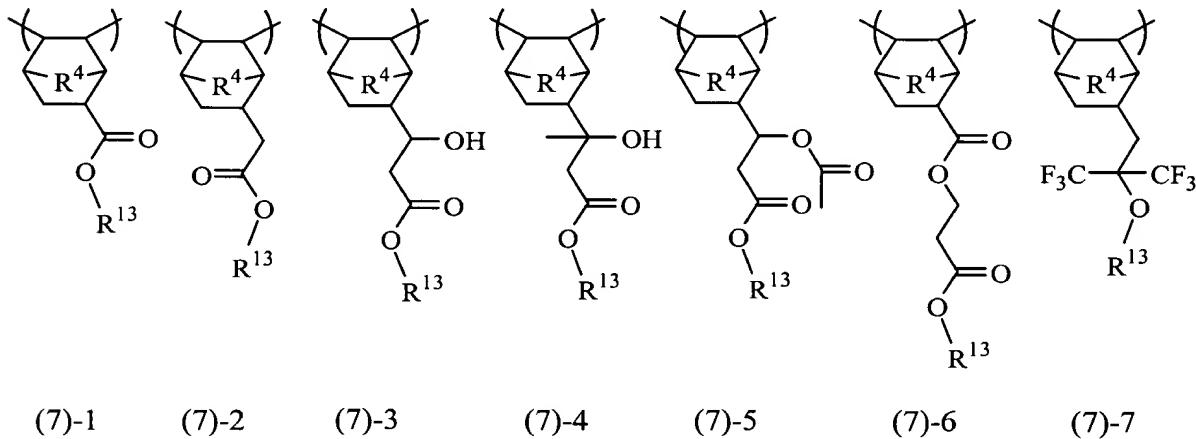
16. (Previously Presented): A polymer comprising recurring units of a compound

of formula (1):



wherein A is a divalent aliphatic or alicyclic hydrocarbon group of 2 to 20 carbon atoms, R<sup>1</sup> is an alkyl group containing at least one fluorine atom, and which optionally contains a hetero atom, "a" is a positive number of 1 to 3, R is a single bond, methylene group, oxygen atom, NH group or sulfur atom, and R<sup>2</sup> and R<sup>3</sup> each are a single bond or methylene group,

said compound further comprising recurring units of a norbornene compound selected from formulae (7)-1, (7)-2, (7)-3, (7)-4, (7)-5, (7)-6, and (7)-7

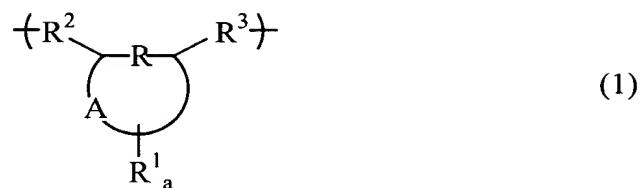


wherein

R<sup>4</sup> is a methylene group, oxygen atom, NH group or sulfur atom, and

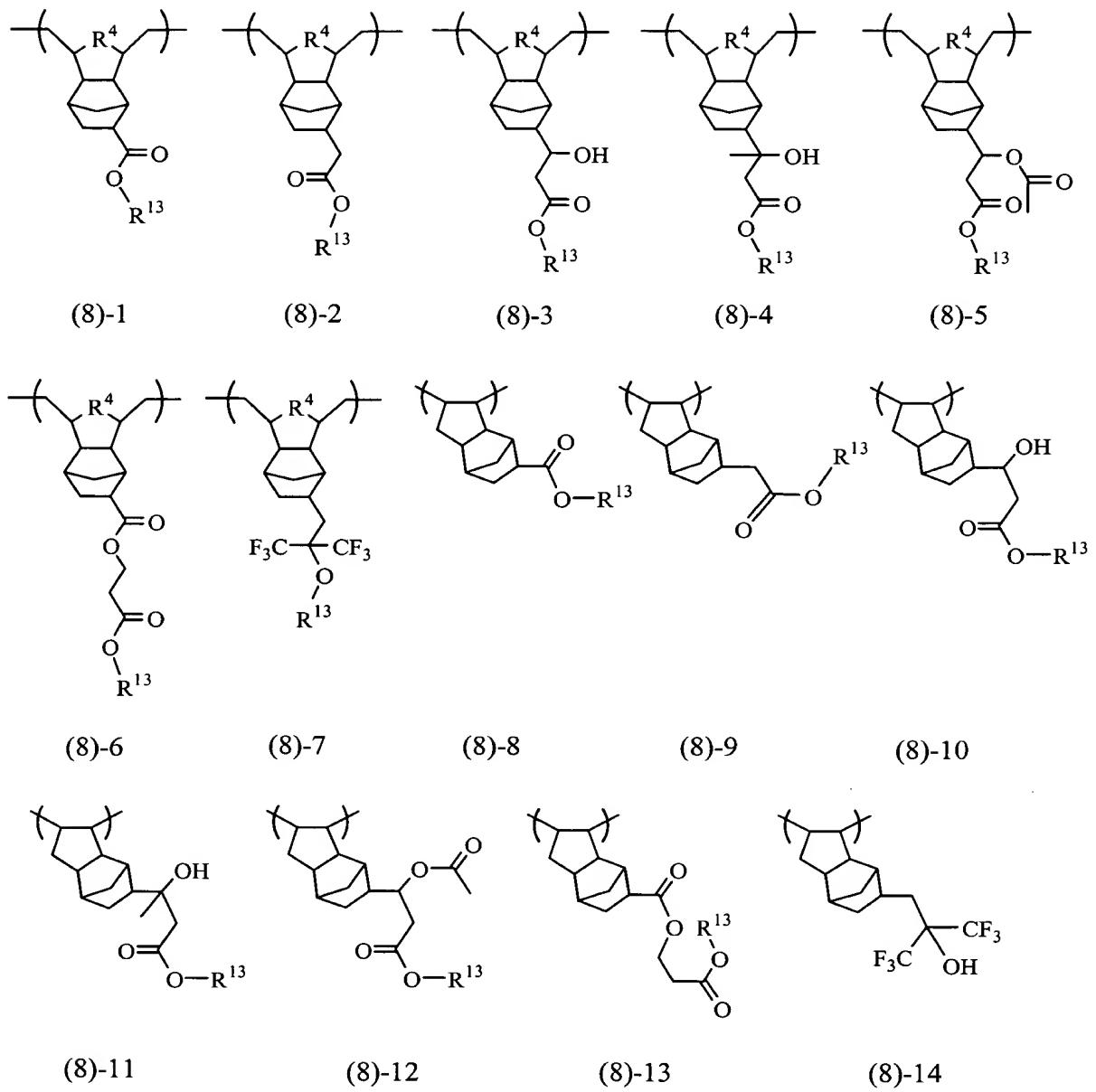
R<sup>13</sup> is an acid labile group.

17. (Previously Presented): A polymer comprising recurring units of a compound of formula (1):



wherein A is a divalent aliphatic or alicyclic hydrocarbon group of 2 to 20 carbon atoms, R<sup>1</sup> is an alkyl group containing at least one fluorine atom, and which optionally contains a hetero atom, "a" is a positive number of 1 to 3, R is a single bond, methylene group, oxygen atom, NH group or sulfur atom, and R<sup>2</sup> and R<sup>3</sup> each are a single bond or methylene group,

said compound further comprising recurring units of a tricyclodecene compound selected from formulae (8)-1, (8)-2, (8)-3, (8)-4, (8)-5, (8)-6, (8)-7, (8)-8, (8)-9, (8)-10, (8)-11, (8)-12, (8)-13, and (8)-14

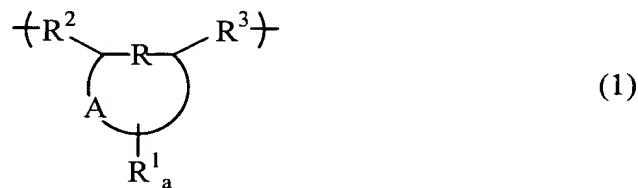


wherein

$R^4$  is a methylene group, oxygen atom, NH group or sulfur atom, and

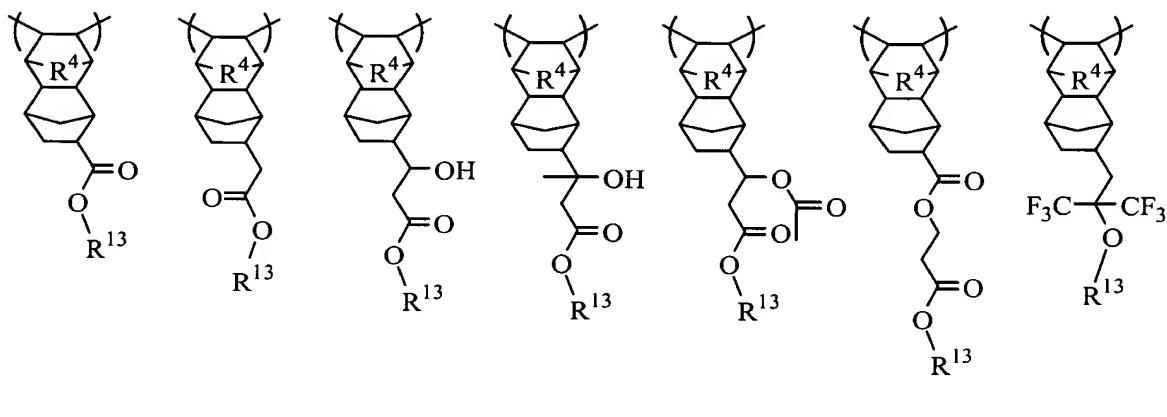
$R^{13}$  is an acid labile group.

18. (Previously Presented): A polymer comprising recurring units of a compound of formula (1):



wherein A is a divalent aliphatic or alicyclic hydrocarbon group of 2 to 20 carbon atoms, R<sup>1</sup> is an alkyl group containing at least one fluorine atom, and which optionally contains a hetero atom, "a" is a positive number of 1 to 3, R is a single bond, methylene group, oxygen atom, NH group or sulfur atom, and R<sup>2</sup> and R<sup>3</sup> each are a single bond or methylene group,

said compound further comprising recurring units of a tetracyclododecene compound selected from formulae (9)-1, (9)-2, (9)-3, (9)-4, (9)-5, (9)-6, and (9)-7

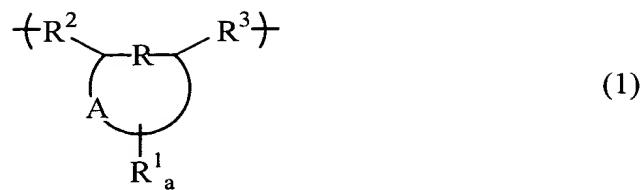


wherein

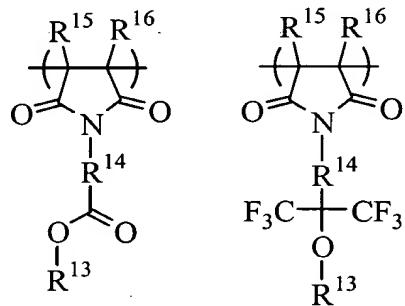
R<sup>4</sup> is a methylene group, oxygen atom, NH group or sulfur atom, and

R<sup>13</sup> is an acid labile group.

19. (Previously Presented): A polymer comprising recurring units of a compound of formula (1):



wherein A is a divalent aliphatic or alicyclic hydrocarbon group of 2 to 20 carbon atoms, R<sup>1</sup> is an alkyl group containing at least one fluorine atom, and which optionally contains a hetero atom, "a" is a positive number of 1 to 3, R is a single bond, methylene group, oxygen atom, NH group or sulfur atom, and R<sup>2</sup> and R<sup>3</sup> each are a single bond or methylene group, said compound further comprising recurring units of a maleimide compound of formula (10)-1 or (10)-2



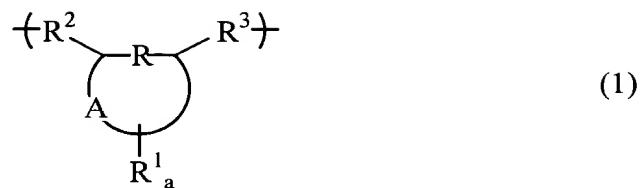
wherein

R<sup>13</sup> is an acid labile group,

R<sup>14</sup> is a single bond or an alkylene group of 1 to 10 carbon atoms, and

R<sup>15</sup> and R<sup>16</sup> are, each independently, hydrogen, fluorine, methyl or trifluoromethyl.

20. (Previously Presented): A polymer comprising recurring units of a compound of formula (1):



wherein A is a divalent aliphatic or alicyclic hydrocarbon group of 2 to 20 carbon atoms, R<sup>1</sup> is an alkyl group containing at least one fluorine atom, and which optionally contains a hetero atom, "a" is a positive number of 1 to 3, R is a single bond, methylene group, oxygen atom, NH group or sulfur atom, and R<sup>2</sup> and R<sup>3</sup> each are a single bond or methylene group,  
said compound further comprising recurring units of a vinyl alcohol compound of formula  
(11)



wherein

R<sup>13</sup> is an acid labile group, and

R<sup>14</sup>, R<sup>15</sup> and R<sup>16</sup> are, each independently, a hydrogen atom, fluorine atom, or a straight, branched or cyclic alkyl group of 1 to 10 carbon atoms, which are, each independently, optionally substituted with fluorine.

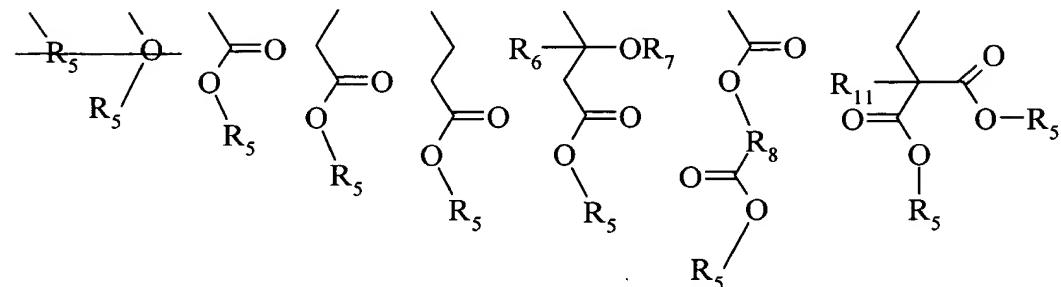
21. (Previously Presented): A polymer according to claim 1, wherein said polymer has a weight average molecular weight of 1,000 to 1,000,000.

22. (Previously Presented): In a process of preparing a polymer, the improvement wherein a monomer of formula (1) of claim 1 is used.

23. (Previously Presented): In a process of forming a resist composition or a resist pattern, the improvement wherein a polymer of claim 1 is used.

24. (Cancelled):

25. (Currently Amended): A polymer of claim 1, wherein  
R<sup>1</sup> is selected from formulae (3)-1, (3)-2, (3)-3, (3)-4, (3)-5, (3)-6, (3)-7, and (3)-9



(3)-1 (3)-2 (3)-3 (3)-4 (3)-5 (3)-6 (3)-7 (3)-8 (3)-9

R<sup>5</sup> is a fluorinated alkyl group which optionally contains an ether or ester bond,  
R<sup>6</sup> and R<sup>11</sup> are, each independently, hydrogen or a straight alkyl group of 1 to 10 carbon atoms,  
R<sup>7</sup> is hydrogen, a straight alkyl group of 1 to 10 carbon atoms, or -C=O-R<sup>12</sup>,  
R<sup>12</sup> is hydrogen or a straight alkyl group of 1 to 10 carbon atoms, and  
R<sup>8</sup> is an alkylene group of 1 to 10 carbon atoms.

26. (Previously Presented): A polymer according to claim 25, further comprising recurring units containing acid labile groups.

27. (Previously Presented): A chemically amplified resist composition comprising a polymer according to claim 25.

28. (Previously Presented): A chemically amplified positive resist composition comprising

- (A) the polymer of claim 25,
- (B) an organic solvent, and
- (C) a photoacid generator.

29. (Previously Presented): A resist composition according to claim 28, further comprising a basic compound.

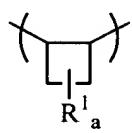
30. (Previously Presented): A resist composition according to claim 28, further comprising a dissolution inhibitor.

31. (Previously Presented): A process for forming a resist pattern comprising the steps of:

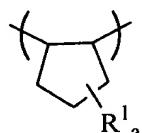
applying a resist composition according to claim 28 onto a substrate to form a coating,  
heat treating the coating and then exposing it to high-energy radiation having a wavelength of up to 180 nm or electron beams through a photo mask, and  
optionally heat treating the exposed coating and developing it with a developer.

32. (Previously Presented): A polymer of claim 25, wherein R is a single bond or methylene.

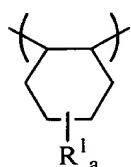
33. (Currently Amended): A polymer of claim 25 †, wherein the recurring units of formula (1) are selected from formulae (2)-1, (2)-2, (2)-3, (2)-4, (2)-5, (2)-6, (2)-7, (2)-8, and (2)-9



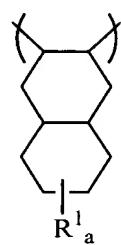
(2)-1



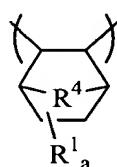
(2)-2



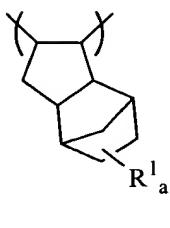
(2)-3



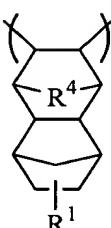
(2)-4



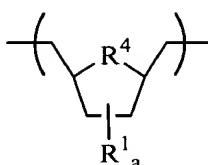
(2)-5



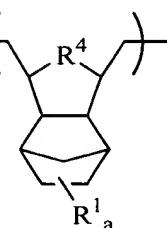
(2)-6



(2)-7



(2)-8



(2)-9

wherein

R<sup>4</sup> is a methylene group, oxygen atom, NH group or sulfur atom, and

“a” is a positive number of 1 to 3.